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IN THE CLAIMS

Please amend claims 1-5 and 7-13 as follows.

1. (Currently amended) A method of seasoning a process chamber having interior surfaces, comprising the steps of:

cleaning said process chamber; and

providing a seasoning film having a thickness of from about 2  $\mu\text{m}$  to about 10  $\mu\text{m}$  on said interior surfaces of said process chamber by introducing precursor gases selected from the group consisting of silane and an oxygen-containing gas, dichlorosilane and a nitrogen-containing gas and trimethyl silane and a carbon-containing gas into said process chamber at a chamber pressure of from about 10 Torr to about 760 Torr.

2. (Currently amended) The method of claim 1 wherein said seasoning film comprises ~~oxide-based material~~ silicon dioxide and said precursor gases comprise said silane and said oxygen-containing gas.

3. (Currently amended) The method of claim 1 wherein said seasoning film comprises silicon nitride and said precursor gases comprise said dichlorosilane and said nitrogen-containing gas.

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4. (Currently amended) The method of claim 1 wherein said seasoning film comprises silicon carbide and said precursor gases comprise said trimethyl silane and said carbon-containing gas.

5. (Currently amended) A method of seasoning a chemical vapor deposition chamber having interior surfaces and a gas distribution plate, comprising the steps of:

cleaning said chamber; and

providing a seasoning film having a thickness of from about 2  $\mu\text{m}$  to about 10  $\mu\text{m}$  on said interior surfaces and said gas distribution plate of said chamber by introducing precursor gases selected from the group consisting of silane and an oxygen-containing gas, dichlorosilane and a nitrogen-containing gas and trimethyl silane and a carbon-containing gas into said process chamber at a chamber pressure of from about 10 Torr to about 760 Torr at a temperature of from about 500 degrees C to about 700 degrees C.

6. (Previously presented) The method of claim 5 wherein said seasoning film comprises oxide-based material.

7. (Currently amended) The method of claim 5 wherein said seasoning film comprises silicon dioxide and said precursor gases comprise said silane and said oxygen-containing gas.

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8. (Currently amended) The method of claim 5 wherein said seasoning film comprises silicon nitride and said precursor gases comprise said dichlorosilane and said nitrogen-containing gas.

9. (Currently amended) The method of claim 5 wherein said seasoning film comprises silicon carbide and said precursor gases comprise said trimethyl silane and said carbon-containing gas.

10. (Currently amended) A method of seasoning a chemical vapor deposition chamber having interior surfaces and a gas distribution plate, comprising the steps of:

cleaning said chamber; and

providing a seasoning film having a thickness of from about 2  $\mu\text{m}$  to about 10  $\mu\text{m}$  on said interior surfaces and said gas distribution plate of said chamber by introducing seasoning film precursor gases selected from the group consisting of silane and an oxygen-containing gas, dichlorosilane and a nitrogen-containing gas and trimethyl silane and a carbon-containing gas into said chamber at a chamber pressure of from about 10 Torr to about 760 Torr at a temperature of from about 500 degrees C to about 700 degrees C and a process time of from about 0.5 minutes to about 10 minutes.

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11. (Currently amended) The method of claim 10 wherein said seasoning film comprises silicon dioxide and said precursor gases comprise said silane and said oxygen-containing gas.

12. (Currently amended) The method of claim 10 wherein said seasoning film comprises silicon nitride and said precursor gases comprise said dichlorosilane and said nitrogen-containing gas.

13. (Currently amended) The method of claim 10 wherein said seasoning film comprises silicon carbide and said precursor gases comprise said trimethyl silane and said carbon-containing gas.